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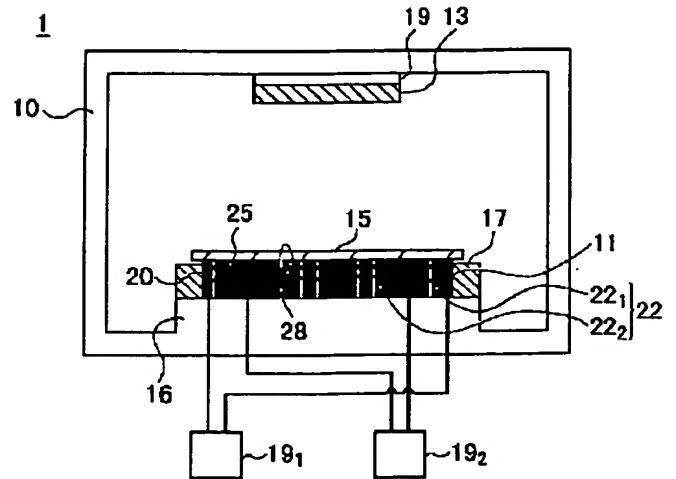
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TITLE : HOTPLATE



ABSTRACT : PROBLEM TO BE SOLVED: To provide a hotplate of a structure, wherein a substrate is made to heat up at a uniform temperature.

SOLUTION: In a vacuum device 1 having a vacuum tank 10, a heater 22, which is provided in a unit main body 20 of a hotplate 11, is constituted in such a way that the temperature of the outer peripheral part of a suction surface 28 and the temperature of the part on the side more inner than the outer periphery part can be separately set. For example, the heater 22 is split, the outer peripheral parts of the split heaters 22 are respectively constituted of an annular first heater pattern 22₁, and the interiors of the outer peripheral parts are respectively constituted of a second heater pattern 22₂. In the case where a substrate 15 is electrostatically adsorbed on the suction surface 28 to heat the substrate 15, the temperature of the peripheral part of the substrate 15 is apt to be reduced lower than that of the part other than the peripheral part, but the substrate 15 is evenly heated up if the heat generation quantity of the first heater patterns 22₁ are held increased.

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